L Number	Hits	Search Text	DB	Time stamp
1	16740	ono	USPAT	2003/02/14 14:36
3	5210	ono and semiconductor	USPAT	2003/02/14 14:36
4	816	ono same (photoresist or mask)	USPAT	2003/02/14 14:38
5	772	(ono same (photoresist or mask)) and semiconductor	USPAT	2003/02/14 14:39
6	761	<pre>((ono same (photoresist or mask)) and semiconductor) and (remov\$ or strip\$4 or polish\$4)</pre>	USPAT	2003/02/14 14:38
7	556	ono same (photoresist or mask) same (remov\$3 or strip\$4 or polish\$4)	USPAT	2003/02/14 14:40
8	526	<pre>(ono same (photoresist or mask) same (remov\$3 or strip\$4 or polish\$4)) and semiconductor</pre>	USPAT	2003/02/14 14:40
9	452	((ono same (photoresist or mask) same (remov\$3 or strip\$4 or polish\$4)) and semiconductor) and pattern\$4	USPAT	2003/02/14 14:40
10	250	ono same (photoresist or mask) same (remov\$3 or strip\$4 or polish\$4) same pattern\$4	USPAT	2003/02/14 14:40
11	237	<pre>(ono same (photoresist or mask) same (remov\$3 or strip\$4 or polish\$4) same pattern\$4) and semiconductor</pre>	USPAT	2003/02/14 14:40

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